

ABSTRACT OF THE DISCLOSURE

It is an object of the present invention to provide a structure capable of determining a failed part of a semiconductor device in sufficient detail. An n^+ impurity region (3) and a p^+ impurity region (4) are connected with each other and further connected with a peripheral circuit (50). A gate electrode (1) and a gate electrode (10) are connected with each other and further connected with the peripheral circuit (50). A ground potential (8) is applied to an n^+ impurity region (2) and a p^- well region (6). A power source potential (9) is applied to a p^+ impurity region (5) and an n^- well region (7).

10 An n^+ impurity region (23) and a p^+ impurity region (24) are connected with each other and further connected with the gate electrode (10) through a metal wire (31). The ground potential (8) is applied to a p^- well region (26) and the power source potential (9) is applied to an n^- well region (27).

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